Amendments to the Claims:

This listing of claims replaces all prior versions and listings of claims in the application:

1. (currently amended) A device for holding a nanolithography template used for imprinting a nanolithography pattern on a substrate, said device comprising:

a body having an opening to receive said nanolithography template, said body for positioning said template relative to said substrate for imprinting said nanolithography pattern on said substrate; and

a supporting plate coupled to said body and positioned relative to said nanolithography template to support a force of said imprinting on said nanolithography template, with said supporting plate being substantially transparent to a curing agent.

2. (original) The device as recited in claim 1 wherein said curing agent comprises ultraviolet radiation.

3. (original) The device as recited in claim 1 wherein said supporting plate is formed from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.

4. (currently amended) The device as recited in claim 1 further including a vacuum system in fluid communication with said supporting plate to apply a vacuum to said nanolithography template.

5. (original) The device as recited in claim 1 further including a vacuum system in fluid communication with said supporting plate to apply a vacuum between said supporting plate and said body.

6. (currently amended) The device as recited in claim 1 wherein said supporting plate is configured to reduce deformation of said nanolithography template due to forces present during an imprint lithography process.

7. (original) The device as recited in claim 1 further including a reflective element connected to a portion of said body located within said opening.

8. (currently amended) A device for holding a nanolithography template used for imprinting a nanolithography pattern on a substrate, said device comprising:

a body having an opening to receive said nanolithography template, said body for positioning said template relative to said substrate for for imprinting said nanolithography pattern on said substrate; and

a supporting plate coupled to said body and positioned relative to said nanolithography template to support a force of said imprinting on said nanolithography template, with said supporting plate substantially transparent to ultraviolet radiation.

9. (original) The device as recited in claim 8 wherein said supporting plate is formed from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.

10. (currently amended) The device as recited in claim [[181]] 8 further including a vacuum system in fluid communication with said supporting plate to apply a vacuum to said nanolithography template.

11. (original) The device as recited in claim 8 further including a vacuum system in fluid communication with said supporting plate to apply a vacuum between said supporting plate and said body.

12. (currently amended) The device as recited in claim 8 wherein said supporting plate is configured to reduce deformation of said nanolithography template due to forces present during an imprint lithography process.

13. (original) The device as recited in claim 8 further including a reflective element connected to a portion of said body located within said opening.

14. (currently amended) A device for holding a nanolithography template used for imprinting a nanolithography pattern on a substrate, said device comprising:

a body having an opening to receive said nanolithography template, said body for positioning said template relative to said substrate for imprinting said nanolithography pattern on said substrate;

a supporting plate coupled to said body and positioned relative to said nanolithography template to support a force of said imprinting on said nanolithography template, with said supporting plate substantially transparent to a curing agent; and

a vacuum system in fluid communication with said supporting plate to apply a vacuum between said supporting plate and said body.

15. (original) The device as recited in claim 14 wherein said curing agent comprises ultraviolet radiation.

16. (original) The device as recited in claim 14 wherein said supporting plate is formed from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.

17. (currently amended) The device as recited in claim 14 wherein said supporting plate is configured to reduce deformation of said nanolithography template due to forces present during an imprint lithography process.

18. (original) The device as recited in claim 14 further including a reflective element connected to a portion of said body located within said opening.